

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	10	LISENKER-B LISENKER-BORIS-S LISENKER-B-S	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/12/16 14:01
L2	3	JANKELEVICH	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/12/16 14:02
L3	32	KIZILYALLI and deuter\$8	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/12/16 14:03
L4	15	(438/301.ccls. 438/303.ccls. 438/595.ccls. 438/786.ccls. 438/791.ccls. 427/255.29.ccls. 427/255.39.ccls. 427/255.393. ccls. 427/255.394.ccls.) and deuter\$8	US-PGPUB; USPAT	OR	ON	2004/12/16 14:14
L5	11	deuter\$8 and (tetrachlorosilane tcs "sicl.sub.4" hexachlorodisilane hcd "si.sub.2 cl.sub.6" "si.sub.2cl.sub. 6")	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/16 14:21
L6	159	deuter\$8 and (cvd (chemical adj vapor)) and (tetrachlorosilane tcs "sicl.sub.4" hexachlorodisilane hcd "si.sub.2 cl.sub.6" "si.sub.2cl.sub. 6")	US-PGPUB; USPAT	OR	ON	2004/12/16 14:23
L7	29	deuter\$8 and ((silicon adj (oxynitride nitride)) sion sio?n? si?n? "si.sub.3 n.sub.4" "si.sub.3n. sub.4")	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/16 14:44
L8	55	deuter\$8 same (cvd (chemical adj vapor)) same ((silicon adj (oxynitride nitride)) sion sio?n? si?n? "si.sub.3 n.sub.4" "si.sub.3n. sub.4")	US-PGPUB; USPAT	OR	ON	2004/12/16 14:50
L9	9	deuter\$8 and ((silicon adj oxynitride) sino sion sio?n? "sio. sub.xn.sub.y" "sio.sub.x n.sub.y" "sin.sub.xo.sub.y" "sin.sub.x o. sub.y" "si.sub.xo.sub.yn.sub.z" "si. sub.x o.sub.y n.sub.z" "si.sub.xn. sub.yo.sub.z" "si.sub.x n.sub.y o. sub.z")	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/16 15:00

L10	32	deuter\$8 same ((silicon adj oxynitride) sino sion sio?n? "sio. sub.xn.sub.y" "sio.sub.x n.sub.y" "sin.sub.xo.sub.y" "sin.sub.x o. sub.y" "si.sub.xo.sub.yn.sub.z" "si. sub.x o.sub.y n.sub.z" "si.sub.xn. sub.yo.sub.z" "si.sub.x n.sub.y o. sub.z")	US-PGPUB; USPAT	OR	ON	2004/12/16 15:02
L11	146	(spacer near nitride) same (etch\$6 with (gas dry vertical\$4 anisotropic\$8)) same ((source drain) with implant\$8)	US-PGPUB; USPAT	OR	ON	2004/12/16 15:08
L12	49	((spacer near nitride) same (etch\$6 with (gas dry vertical\$4 anisotropic\$8)) same ((source drain) with implant\$8)) and dram	US-PGPUB; USPAT	OR	ON	2004/12/16 15:11
L13	3820	438/301.ccls. 438/303.ccls. 438/595.ccls. 438/786.ccls. 438/791.ccls. 427/255.29.ccls. 427/255.39.ccls. 427/255.393. ccls. 427/255.394.ccls.	US-PGPUB; USPAT	OR	OFF	2004/12/16 15:13
L14	2327	13 and (deuter\$8 (silicon adj (oxynitride nitride)) sion sio?n? si?n? "si.sub.3 n.sub.4" "si.sub.3n. sub.4")	US-PGPUB; USPAT	OR	ON	2004/12/16 15:15
L15	700	13 and (deuter\$8 (silicon adj oxynitride) sion sio?n? si?n?)	US-PGPUB; USPAT	OR	ON	2004/12/16 15:15